

| L Number | Hits | Search Text | DB | Time stamp |
|----------|-------|---|---|------------------|
| 1 | 3748 | silicon same (micro near machin\$3 or "MEMS") | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:51 |
| 2 | 14187 | (photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:01 |
| 3 | 0 | ((silicon same (micro near machin\$3 or "MEMS")) same ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 18:51 |
| 4 | 38 | ((silicon same (micro near machin\$3 or "MEMS")) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 18:52 |
| 5 | 3 | ((silicon same (micro near machin\$3 or "MEMS")) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) and @pd<20000524 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 18:52 |
| 6 | 298 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 20:12 |
| 7 | 45 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and @pd<20000524 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:02 |
| 8 | 17 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:25 |
| 10 | 0 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3) and (backside near etch\$3) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:26 |
| 9 | 12 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:44 |
| 11 | 1 | ("5569355").PN. | USPAT; US-PGPUB | 2003/07/09 19:46 |
| 12 | 17 | (deep near lithograph\$2) same (micro near machin\$3 or "MEMS") | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:56 |
| 13 | 0 | "5569355".pn. and ("MEMS") | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:56 |
| 14 | 561 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2 or lithograph\$2)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 20:12 |

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|----|-----|--|---|------------------|
| 15 | 413 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2 or lithograph\$2)) and (silicon same etch\$3) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 20:14 |
| 16 | 59 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2 or lithograph\$2)) and (silicon same etch\$3)) and @pd<20000524 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 20:16 |

| L Number | Hits | Search Text | DB | Time stamp |
|----------|-------|---|---|------------------|
| 1 | 3748 | silicon same (micro near machin\$3 or "MEMS") | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 18:49 |
| 2 | 14187 | ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:01 |
| 3 | 0 | ((silicon same (micro near machin\$3 or "MEMS")) same ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 18:51 |
| 4 | 38 | ((silicon same (micro near machin\$3 or "MEMS")) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 18:52 |
| 5 | 3 | ((silicon same (micro near machin\$3 or "MEMS")) and ((photo near resist or photolithograph\$2 or image) same (adjust\$3 same focus\$3))) and @pd<20000524 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 18:52 |
| 6 | 298 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:24 |
| 7 | 45 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and @pd<20000524 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:02 |
| 8 | 17 | ((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:25 |
| 10 | 0 | (((((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3) and (backside near etch\$3)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:26 |
| 9 | 12 | (((((silicon same (micro near machin\$3 or "MEMS")) same (photo near resist or photolithograph\$2)) and 216/2.ccls.) and insulat\$3 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/07/09 19:26 |